

## NIST INTERNSHIP OPPORTUNITY

**NEATEC and the National Institute of Standards and Technology (NIST) offer a full semester internship in Semiconductor and Nanotechnology**

**This is an opportunity for students or college graduates to learn about semiconductor and Nanotechnology manufacturing processes by working in one of most advanced center in the Nation. The student will be personally mentored by scientists and engineers at the NIST.**

### NanoFab at CNST/ NIST

The NIST Center for Nanoscale Science and Technology (CNST) supports the development of nanotechnology by providing industry, academia, NIST, and other government agencies access to world-class nanoscale measurement and fabrication methods and tools.

The CNST's NanoLab offers opportunities for researchers to collaborate on creating and using the next generation of nanoscale measurements and fabrication tools and methods.



**Starting Date: September 2018**

**Application deadline: August 1, 2018**

**Duration: 16 weeks**

**Venue: Center of Nanoscale Science and Technology (CNST) Nanofab, at the NIST – Gaithersburg, MD**

### General

- NEATEC will sponsor **only 3** participants
- The NIST will prepare a program based on your Interests and background
- Learn about clean rooms, lithography, deposition, etching, CMP, metrology, etc.

### Who should apply?

- The program is designed for 2-year and/or 4-year Students or college graduates from a technology Program
- Special consideration will be given to students Pursuing careers in Semiconductors, Nanotechnology, Material sciences, Electronics, and other closely related fields.

### Fellowships

**You will receive:**

- A weekly stipend of \$650 for the duration of the Internship (16 weeks)
- An allowance of \$500 for travel expenses

**Apply and register at: [NIST Internship](#)**

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